## AMENDMENTS TO THE CLAIMS

Please amend the claims as follows:

1. (Currently Amended) A focussing lens for focussing a charged particle beam onto a specimen at a predetermined landing angle, comprising:

at least a first electrode having a first aperture to generate a focussing electric field for focussing the charged particle beam onto the specimen; and

a correcting electrode having a cone-like shaped curved surface to compensate for landing angle dependent distortions of the focussing electric field, the distortions being caused by the specimen, wherein the cone-like shaped curved surface of the correcting electrode has an opening on one side to provide space for the specimen to approach the first electrode.

2. (Canceled)

3. (Previously Presented) The focussing lens of claim 1, wherein the curved surface of the correcting electrode has an opening on one side to provide space for the specimen to approach the first electrode.

4. (Previously Presented) The focussing lens of claim 1, wherein the curved surface of the correcting electrode is aligned to be rotationally symmetric with respect to a symmetry axis of the first aperture.

5. (Previously Presented) The focussing lens of claim 1, wherein the curved surface of the correcting electrode encircles a symmetry axis by a covering angle of less than or equal to 350 degrees.

6. (Previously Presented) The focussing lens of claim 1, wherein the curved surface of the correcting electrode encircles a symmetry axis by a covering angle of at least 10 degrees.

7. (Previously Presented) The focussing lens of claim 5, wherein the covering angle is taken within the plane of the first aperture.

8. (Previously Presented) The focussing lens of claim 1, wherein the curved surface of the correcting electrode is rigidly fastened to the at least first electrode.

9. (Previously Presented) The focussing lens of claim 1, wherein the at least first electrode and the correcting electrode are electrically connected to different voltage sources to provide for different voltages.

10. (Previously Presented) The focussing lens of claim 1, wherein the first electrode is cone-like shaped.

11. (Previously Presented) The focussing lens of claim 1, wherein the curved surface of the correcting electrode faces the first electrode conformally.

12. (Previously Presented) The focussing lens of claim 1, wherein a distance D1 between the at least one first electrode and the facing curved surface of the correcting electrode is smaller than 10 mm.

13. (Previously Presented) The focussing lens of claim 1, wherein the at least one first electrode and the correcting electrode are arranged to withstand a voltage of at least 500 V.

14. (Previously Presented) The focussing lens of claim 10, wherein the curved surface of the correcting electrode is shaped and positioned to cover more than 20% of the cone-like shaped first electrode to electrostatically shield said cone-like shaped first electrode.

15. (Currently Amended) The focussing lens of claim 3, wherein the opening of the curved surface of the correcting electrode is large enough to accommodate the specimen closer to the at least one first electrode than ~~the~~ a distance D1 between the first electrode and the curved surface of the correcting electrode.

16. (Previously Presented) The focussing lens of claim 3, wherein a rim of the opening in the curved surface of the correcting electrode defines essentially a parabola.

17. (Previously Presented) The focussing lens of claim 1, wherein the specimen is a planar semiconductor wafer having a diameter larger than 30 mm.

18. (Previously Presented) The focussing lens of claim 2, wherein a vertex angle of the cone-like shaped correcting electrode is is within a range of 30 degrees and 160 degrees.

19. (Previously Presented) The focussing lens of claim 1, further comprising a coil for providing a focussing magnetic field for focussing the charged particle beam.

20. (Previously Presented) The focussing lens of claim 1, further comprising a second electrode having a second aperture for focussing the charged particle beam.

21. (Currently Amended) A charged particle beam device to inspect or structure a specimen at various predetermined landing angles, comprising:

a charged particle beam source to generate a charged particle beam; and

a focussing lens to focus the charged particle beam onto the specimen, the focussing lens comprising at least a first electrode having a first aperture to generate a focussing electric field for focussing the charged particle beam onto the specimen and a correcting electrode having a cone-like shaped curved surface to compensate for landing angle dependent distortions of the focussing electric field, the distortions being caused by the specimen, wherein the cone-like shaped curved surface of the correcting

electrode has an opening on one side to provide space for the specimen to approach the first electrode.

22. (Previously Presented) The charged particle beam device of claim 21, further comprising a tilting mechanism to tilt a symmetry axis of the focussing lens with respect to the surface of the specimen for inspecting or structuring the specimen between at least two different landing angles.

23. (Previously Presented) The charged particle beam device of claim 22, wherein the tilting mechanism is capable of tilting the symmetry axis of the focussing lens to provide a vertical landing angle and a tilted landing angle which deviates from the vertical landing angle by at least 20.

24. (Previously Presented) The charged particle beam device of claim 22, wherein the tilting mechanism is capable of providing a tilted landing angle which is half the cone vertex angle of the cone-like shaped first electrode.

25. (Previously Presented) The charged particle beam device of claim 22, wherein the symmetry plane of the focussing lens is equal to or about equal to the tilting plane.

26-38. (Canceled)